

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3	fum\$3 with ( silica or sio2 or "sio.sub.2") same shake with ( size or diameter)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:31
S2	6	fum\$3 with ( silica or sio2 or "sio.sub.2") and shake with( size or diameter)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:32
S3	0	10/594635	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:33
S4	145	fum\$3 with( silica or sio2 or "sio.sub.2") same dispersibility	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:37
S5	63	fum\$3 with( silica or sio2 or "sio.sub.2") with dispersibility	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:37
S6	12	fum\$3 with( silica or sio2 or "sio.sub.2") with dispersibility and semi\$1conduct\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:37
S7	3842	fum\$3 with( silica or sio2 or "sio.sub.2") with acid\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:55
S8	146	fum\$3 with( silica or sio2 or "sio.sub.2") with acid\$3 same ( dispersibility or stability or stable)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 14:55
S9	72	fum\$3 with( silica or sio2 or "sio.sub.2") with ph with ( base or basic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 15:28

S10	96	fumed adj silica with bet with nm	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 16:11
S11	190	fumed adj silica with nm same polish\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 16:15
S12	93	fumed adj silica with nm same polish\$3 and ( surface adj area or bet)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 16:15
S13	153	fumed adj silica and fukuda	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 16:20
S14	6	fumed adj silica and fukuda and shake	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 16:20
S15	4	fumed adj silica.ti. and fukuda	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/10 16:21
S16	47	fumed adj silica same semiconductor and bet and silica with ( size or diameter)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/27 14:25
S17	299	fumed adj silica with nm and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/27 16:21
S18	246	fumed adj silica with nm and semiconductor same polishing	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/27 16:21
S19	53067	fumed adj silica with nm same betand semiconductor same polishing	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/27 16:22

S20	30	fumed adj silica with nm same bet and semiconductor same polishing	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/27 16:22
S21	30	fumed adj silica with nm same (better benefit\$3 increase increased decrease decreased improv\$5 enhanc\$3 prefer\$3) and semiconductor same polishing	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/27 16:38

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